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**The effect of a planar antenna on a ferromagnetic core ICP** JIN YOUNG BANG, SUNG WON CHO, CHIN WOOK CHUNG, PNA TEAM — A side type ferrite inductively coupled plasmas (ICPs) with high efficiency and low voltage suitable for next generation processing was recently developed [1]. In this ICP, the plasma density at edge of the chamber is higher than center of the chamber because the region where the plasma generation is localized at the edge of the chamber. To control plasma uniformity in various environments, an additional planar antenna on the top of the chamber was installed at the center to increase the center density and the effect of the additional antenna was analyzed.

[1] K. H. Lee, Y. K. Lee, S. W. Lee, C.W. Chung, Gases Electron Conference 2006.

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